



Metal-Organic Pulsed Laser Deposition For Stoichiometric Complex Oxide Thin Films

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The Invention

Methods and systems for forming complex oxide films are provided. Also provided are complex oxide films and heterostructures made using the methods and electronic devices incorporating the complex oxide films and heterostructures. In the methods pulsed laser deposition is conducted in an atmosphere containing a metal-organic precursor to form highly stoichiometric complex oxides.

Additional Information

For More Information About the Inventors

- [Chang-Beom Eom](#)

Tech Fields

- [Materials & Chemicals : Metals](#)
- [Materials & Chemicals : Synthesis](#)
- [Semiconductors & Integrated Circuits : Components & materials](#)

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